

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1.-33. (canceled).

34. (previously presented): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents is two or more of propylene glycol monomethyl ether, propylene glycol monomethyl ether acetate, butyl acetate, ethyl 3-ethoxypropionate, methyl 3-methoxypropionate, and cyclohexanone;

wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover;

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises a solvent naphtha.

35. (canceled).

36. (currently amended): A photosensitive composition remover ~~as set forth in claim 35~~ used for removal of an uncured photosensitive composition, which remover consists

essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents is at least one selected from the group consisting of glycol ethers excluding dipropylene glycol monomethyl ether, glycol ether carboxylates, carboxylic acid esters excluding ethyl acetate and amyl acetate, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers; and

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises at least one selected from the group consisting of a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent,

wherein 30 to 60 percent by mass of propylene glycol monomethyl ether is present in the remover.

37. (canceled).

38. (canceled).

39. (canceled).

40. (previously presented): A photosensitive composition remover as set forth in claim 36, wherein the other solvent other than aprotic polar solvents other than propylene glycol monomethyl ether is at least one selected from the group consisting of propylene glycol

monomethyl ether acetate, butyl acetate, cyclohexanone, methyl 3-methoxypropionate and ethyl 3-ethoxypropionate.

41. (previously presented): A photosensitive composition remover used for removal of an uncured photosensitive composition, which remover consists essentially of 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9 carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than aprotic polar solvents,

wherein the aromatic hydrocarbon is basically C₉ or C₁₀-based,

wherein the photosensitive composition remover is used for removal of a photosensitive composition containing a pigment;

wherein the other solvent other than aprotic polar solvents comprises a glycol monoalkyl ether and at least one selected from the group consisting of glycol ether carboxylates, carboxylic acid esters, hydroxycarboxylic acid esters, ketones, alkoxycarboxylic acids esters, and cyclic ethers; and

wherein the aromatic hydrocarbon which is basically C₉ or C₁₀-based comprises at least one selected from the group consisting of a basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent.

42. (canceled).

43. (canceled).

44. (canceled).

45. (canceled).

46. (canceled).

47. (currently amended): A photosensitive composition remover ~~as set forth in claim~~
~~42~~ used for removal of an uncured photosensitive composition, which remover comprises 10 to
20 percent by mass of at least one type of aromatic hydrocarbon having 9 carbon atoms or more
within the molecule and 80 to 90 percent by mass of one or more other solvent(s) other than
aprotic polar solvents, wherein the at least one type of aromatic hydrocarbon having 9 carbon
atoms or more within the molecule comprises at least one selected from the group consisting of a
basically C₉ alkylbenzene-based mixed solvent, a basically C₁₀ alkylbenzene-based mixed
solvent, and a basically C₁₀ alkylbenzene-alkylnaphthalene-based mixed solvent,
~~comprising 10 to 20 percent by mass of one or more aromatic hydrocarbon(s) having 9~~
~~carbon atoms or more within the molecule and 80 to 90 percent by mass of one or more other~~
~~solvent(s) other than aprotic polar solvents, wherein the remover comprises 30 to 60 percent by~~
~~mass of propylene glycol monomethyl ether.~~

48. (canceled).

49. (canceled).

50. (canceled).

51. (previously presented): A photosensitive composition remover as set forth in
claim 47, wherein the other solvent other than aprotic polar solvents is at least one selected from
the group consisting of glycol ethers, glycol ether carboxylates, carboxylic acid esters,
hydroxycarboxylic acid esters, ketones, alcohols, alkoxycarboxylic acids esters, and cyclic
ethers.

52. (canceled).

53. (canceled).